



Serial No. 10/695,743
SEC. 1090

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent application of :
Won-Woong CHOI : Group Art Unit 1756
Serial No. 10/695,743 : Examiner S. Rosasco
Filed October 30, 2003 :

METHOD OF DESIGNING AND MANUFACTURING RETICLES FOR USE IN A
PHOTOLITHOGRAPHIC PROCESS

REQUEST FOR RECONSIDERATION

U.S. Patent and Trademark Office
Customer Service Window, Mail Stop Amendment
Randolph Building
401 Dulany Street
Alexandria VA 22314

Sir:

The following remarks are submitted in response to the Office action of June 28, 2005.

The Office Action of June 28, 2005 and the references cited therein have been carefully studied and reviewed, and in view of the following representations, reconsideration is respectfully requested.

The Examiner is correct in noting that **the claimed invention is drawn to a method of manufacturing a reticle or reticles** used in photolithography to manufacture semiconductor devices. In this respect, alone, the present invention is fundamentally different from the references to Takayama (USP 6,400,839) and Yui et al. (USP 6,455,211) relied on by the Examiner to reject Applicant's claims.